(REV. 1/06)

US Dept. of Commerce PATENT & TRADEMARK OFFICE

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APPLICATION NO. 10/551,130

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

APPLICANT Takahiro KISHIOKA FILING DATE September 29, 2005

GROUP 1756

U.S. PATENT DOCUMENTS

			U.S. PATENT DOC	UMENTS
Examiner Initials	Cite No.	Document Number	Date	Name
CH	1	US 5,919,599	7/6/1999	Meador et al.
CH	2	US 5,693,691	12/2/1997	Flaim et al.
CH	3	US 6,114,085	9/5/2000	Padmanaban et al.
CH	4	US 6,388,039 B1	5/14/2002	Jung et al.
CH	5	US 6,492,092 B1	12/10/2002	Foster et al.
CH	6	US 2002/0093069 A1	7/18/2002	Hong et al.
СН	7	US 2002/0127789 A1	9/12/2002	Hong et al.
CH	8	US 2002/0009595 A1	1/24/2002	Hong ct al.
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		FOR	EIGN PATENT DOC	CUMENTS		
Examiner Initials	Cite No.	Document Number	Date	. Country	With English Abstract	With English Translation
СН	9	JP A 2000-294504	10/20/2000	Japan	×	×
CH	10	JP A 2002-47430	2/12/2002	Japan	×	x
СН	11	JP A 2002-190519	7/5/2002	Japan	×	×
CH	12	WO 02/05035 A1	1/17/2002	WIPO .	×	
CH	13	JP A 2002-128847	5/9/2002	Japan	×	×
CH	14	JA A 11-279523	10/12/1999	Japan	x	×
CH	15	WO 02/086624 A1	10/31/2002	WIPO	×	
CH	.16	JP A 2002-530696	9/17/2002	Japan	×	х
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CH	20	JP A 2002-105137	4/10/2002	Japan	×	×
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CH	22	JP A 2002-97231	4/2/2002	Japan	×	×
CH	23	JP A 2001-194799	7/19/2001	Japan	×	x
ĆН	24	JP A 10-120939	5/12/1998	Japan	×	х
CH	25	JP A 6-118656	4/28/1994	Japan	×	х

Date: May 11, 2006

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Form PTO- (REV. 1/06)	49 AMENTAT	5/ US Dent of Commence	ATTY DOCKET NO. 125473	APPLICATION NO. 10/551,130					
	(Us	e several sheets if necessary)	APPLICANT Takahiro KISHIOKA						
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OTHER DOCUMENTS									
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)							
CH	26	Lynch et al.; "Properties and Performance of Near UV Reflectivity Control Layers;" Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229.							
CH	27	Taylor et al.; "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography;" Proceedings of SPIE, March 1999, Vol. 3678, pp. 174-185.							
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CH	28	Meador et al.; "Recent Progress in 193 nm Antireflective Coatings;" Proceedings of SPIE, March 199, Vol 3678, pp. 800-809.							
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EXAMINER	/Prid	nary Examiner Cynthia Hamil	ton/	OATE CONSIDERED 09/21/2006					
Examiner: Initial injutation considered, whether or not creation is in conformance with M.P.E.P. 609, draw line through citation if not in conformance and not considered. Include copy of this form Anth mext communication to applicant.									
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